

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3405	(high near2 density near2 plasma) near3 (cvd or (chemical adj vapor))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:50
L2	1450	(hdp or hpd) adj (cvd or (chemical adj vapor)) or hdp-cvd or hpd-cvd or hdp-chemical or hpd-chemical	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:51
L3	310573	silicon adj (oxide or dioxide) or ("sio.sub.2")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:52
L4	1526323	semiconduct\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:52
L5	353816	temperature with (celsius or degree\$1)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:53
L6	149975	silane or "sih.sub.4" or sih4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:53
L7	6891	silicon adj fluoride or (sif4) or ("sif.sub.4")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:54
L8	1885	6 same 7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:54

L9	3638	1 or 2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:54
L10	7524	disilane or si2h6 or ("si.sub.2 h. sub.6")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:55
L11	151541	6 or 10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:55
L12	104	9 and 3 and 10 and 4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:55
L13	8	5 and 12	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 16:55
L15	96	12 not 13	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/06 17:17